

## **REMARKS**

In response to the above-identified Office Action, Applicants amend the application and seek reconsideration thereof. In this response, claims 1 and 5 have been amended, no claims have been added and claim 4 has been cancelled. Accordingly, Claims 1-3 and 5-15 are pending.

A method for fabricating a ferroelectric random access memory device, comprising the steps of: (a) forming a first inter-layer insulation layer on a substrate providing a transistor; (b) etching the first inter-layer insulation layer to form a storage node contact hole exposing a partial portion of the substrate; (c) burying a storage node contact including a plug and a barrier metal layer into the storage node contact hole; (d) forming an adhesion layer on the storage node contact and the first inter-layer insulation layer; (e) inducing a predetermined portion of the adhesion layer to be cracked by performing a rapid thermal annealing process, the predetermined portion disposed above an upper part of the plug; (f) selectively removing the cracked predetermined portion to expose a surface of the barrier metal layer formed on the plug; and (g) forming a ferroelectric capacitor connected to the plug through the exposed surface of the barrier metal layer.

### **I. Claim Amendments**

In the instant response, claim 1 is amended to clarify that inducing a predetermined portion of the adhesion layer to be cracked as recited in step (e) is accomplished "by performing a rapid thermal annealing process." Applicant respectfully submits this element was previously recited in now cancelled claim 4 and therefore is supported by the specification and does not add new matter. Claim 5 is amended to depend from claim 1 instead of cancelled claim 4. In view of the foregoing, Applicant respectfully requests consideration and entry of the amendments to claims 1 and 5.

## II. Claims Rejected Under 35 U.S.C. §103(a)

The Examiner rejects claims 1-3 and 6-15 under 35 U.S.C. 103(a) as being obvious over Applicant's alleged admitted prior art and U.S. Patent No. 5,178,725 to Takeno ("Takeno"). Applicant respectfully traverses the rejection for at least the foregoing reasons.

To render a claim obvious, the relied upon references must teach or suggest every limitation of the claim such that the invention as a whole would have been obvious at the time the invention was made to one skilled in the art.

Takeno discloses an irradiation process of irradiating laser beam to the base material, which consists of a ceramic material, in order to form an affected portion having a crack.

In regard to independent claim 1, Takeno fails to teach or suggest at least the element of inducing a crack in the adhesion layer by performing a rapid thermal annealing process as recited in amended claim 1. As previously discussed, claim 1 is amended to include the step of "performing a rapid thermal annealing process" originally set forth in now cancelled claim 4. The Examiner determines in the Action that claim 4 would be allowable if rewritten in independent form including all the limitations of the base claim (claim 1). The Examiner further admits this element of amended claim 1 is not found in the prior art in stating that "the prior art does not teach or suggest a process including the step of forming the crack in the adhesion layer by performing a rapid thermal annealing." See Action, page 4, paragraph 5.

For at least the foregoing reasons, Takeno in view of the AAPA may not be relied upon to teach or suggest the rapid thermal annealing process as recited in claim 1. Since neither Takeno nor AAPA, alone or in combination, teach each and every element of claim 1, a *prima facie* case of obviousness may not be established. For the foregoing

reasons, Applicant respectfully requests reconsideration and withdrawal of the rejection of claim 1 under 35 U.S.C. §103 over Takeno in view of AAPA.

Claims 2-3 and 6-15 depend from claim 1 and incorporate the limitations thereof. Thus for at least the reason that Takeno in view of AAPA fail to teach or suggest each of the elements of claim 1, claims 2-3 and 6-15 may not be found *prima facie* obvious over the references. For the foregoing reasons, Applicant respectfully requests reconsideration and withdrawal of the rejection of claims 2-3 and 6-15 under 35 U.S.C. §103 over Takeno in view of AAPA.

### III. Allowable Subject Matter

Applicant notes with appreciation the Examiner's indication that claims 4-5 would be allowable if rewritten in independent form to include all of the limitations of the base claims and any intervening claims. Claim 4 is cancelled in the instant response and the limitation of performing a rapid thermal annealing process of original claim 4 has been incorporated into amended claim 1. Claim 5 is rewritten to depend from Claim 1 and incorporates the limitations thereof. Accordingly, Applicant respectfully submits claim 5 is allowable without being rewritten to include all the limitations of the base claim and any intervening claims as suggested by the Examiner at least for the reason that it depends from an allowable base claim.

## CONCLUSION

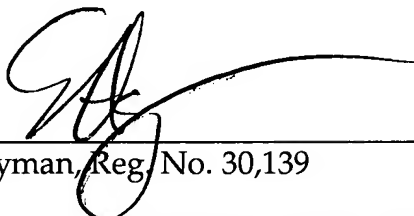
In view of the foregoing, it is believed that all claims now pending, namely claims 1-3 and 5-15 patentably define the subject invention over the prior art of record, and are in condition for allowance and such action is earnestly solicited at the earliest possible date. If the Examiner believes that a telephone conference would be useful in moving the application forward to allowance, the Examiner is encouraged to contact the undersigned at (310) 207 3800.

Respectfully submitted,

BLAKELY, SOKOLOFF, TAYLOR & ZAFMAN LLP

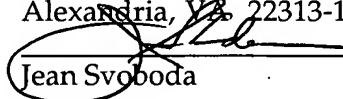
Dated: November 8, 2005

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### CERTIFICATE OF MAILING:

I hereby certify that this correspondence is being deposited with the United States Postal Service as first class mail in an envelope addressed to: Mail Stop Amendment, Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450, on November 8, 2005.

  
Jean Svoboda